

**Notice of References Cited**Application/Control No.  
09/776,329Applicant(s)/Patent Under  
Reexamination  
SEUTTER ET AL.Examiner  
Toniae M. ThomasArt Unit  
2822

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**U.S. PATENT DOCUMENTS**

| * |   | Document Number<br>Country Code-Number-Kind Code | Date<br>MM-YYYY | Name           | Classification |
|---|---|--|-----------------|----------------|----------------|
|   | A | US-2002/0094632 A1                               | 07-2002         | Agarwal et al. | 438/239        |
|   | B | US-6,001,415 B1                                  | 12-1999         | Nogami et al.  | 427/97         |
|   | C | US-6,428,859 B1                                  | 08-2002         | Chiang et al.  | 427/457        |
|   | D | US-  |                 |                |                |
|   | E | US-  |                 |                |                |
|   | F | US-  |                 |                |                |
|   | G | US-  |                 |                |                |
|   | H | US-  |                 |                |                |
|   | I | US-  |                 |                |                |
|   | J | US-  |                 |                |                |
|   | K | US-  |                 |                |                |
|   | L | US-  |                 |                |                |
|   | M | US-  |                 |                |                |

**FOREIGN PATENT DOCUMENTS**

| * |   | Document Number<br>Country Code-Number-Kind Code | Date<br>MM-YYYY | Country | Name | Classification |
|---|---|--|-----------------|---------|------|----------------|
|   | N |  |                 |         |      |                |
|   | O |  |                 |         |      |                |
|   | P |  |                 |         |      |                |
|   | Q |  |                 |         |      |                |
|   | R |  |                 |         |      |                |
|   | S |  |                 |         |      |                |
|   | T |  |                 |         |      |                |

**NON-PATENT DOCUMENTS**

| * |   | Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)   |
|---|---|---|
|   | U | Ritala, M. et al., "Controlled TaN, Ta <sub>3</sub> N <sub>5</sub> , and TaOxNy Thin Films by Atomic Layer Deposition," Chem. Mater., 1999, Vol. 11, pp. 1712-1718. |
|   | V |   |
|   | W |   |
|   | X |   |

\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.